

AMENDMENTS TO THE CLAIMS

Claims 1 – 35 (Cancelled)

36. (Original) A semiconductor device comprising a semiconductor layer which comprises a compound semiconductor using Ga_v, Al_{1-v} , (where, $0 \leq v \leq 1$) as a main component of the Group III-elements and N as a main component of the Group V-elements and a Schottky junction metal layer which is in contact with the semiconductor layer, wherein:

said Schottky junction metal layer comprises a laminated structure wherein a first metal layer is in contact with said semiconductor layer, a second metal layer is in contact with said first metal layer, and a third layer is in contact with said second layer;

said second metal layer comprises a metal material having a higher melting point than those of the metal materials in said first metal layer and said third metal layer;

said third metal layer comprises a metal material having a lower resistivity than those of the metal materials in said first metal layer and said second metal layer;

said first metal layer comprises any metal material selected from a group comprising Ni, Pt, Pd, Ni_z, Si_{1-z} , Pt_z, Si_{1-z} , Pd_z, Si_{1-z} , Ni_z, N_{1-z} , and Pd_z, N_{1-z} , (where, $0 < z < 1$); and

said second metal layer comprises any metal material selected from a group comprising Mo, W, Ta, Mo_x, Si_{1-x} , Pt_x, Si_{1-x} , W_x, Si_{1-x} , Ti_x, Si_{1-x} , Ta_x, Si_{1-x} , Mo_x, N_{1-x} , W_x, N_{1-x} , Ti_x, N_{1-x} , and Ta_x, N_{1-x} , (where, $0 < x < 1$).

37. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein said third metal layer comprises any metal material selected from a group comprising Au, Cu, Al, and Pt.

38. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein said first metal material comprises a metal material having a higher work function than that of the metal material in said second metal material.

39. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 38, wherein said metal layer comprises a metal material having a higher work function than that of the metal material in said third metal layer.

40. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein the melting point of said second metal layer is 1,000°C or higher.

41. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein said semiconductor layer is formed on a multilayered structure comprising a plurality of compound semiconductor layers formed on a substrate.

42. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 41, wherein said substrate comprises any substrate selected from a group comprising a sapphire substrate, a SiC substrate, and a GaN substrate.

43. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein said semiconductor layer is an $\text{Al}_u\text{Ga}_{1-u}\text{N}$ layer (where, $0 \leq u \leq 1$).

44. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein said semiconductor layer is a GaN compound semiconductor electron supplying layer formed on a GaN compound semiconductor channel layer.

45. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 44, wherein said GaN compound semiconductor channel layer comprises a compound semiconductor selected from a group comprising GaN and InGaN, and a GaN compound semiconductor electron supplying layer comprises AlGaN.

46. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein said semiconductor layer is a GaN compound semiconductor channel layer formed on a GaN compound semiconductor electron supplying layer.

47. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 46, wherein said GaN compound semiconductor channel layer comprises a compound semiconductor selected from a group comprising GaN and InGaN, and said GaN compound semiconductor electron supplying layer comprises AlGaN.

48. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 36, wherein said semiconductor layer is a n-type GaN channel layer.

49. (Original) A semiconductor device comprising a semiconductor layer which comprises a compound semiconductor using $\text{Ga}_v\text{Al}_{1-v}$ (where, $0 \leq v \leq 1$) as a main component of the Group III-elements and N as a main component of the Group V-elements and a Schottky junction metal layer which is in contact with the semiconductor layer, wherein:

said Schottky junction metal layer comprises a laminated structure wherein a first metal layer is in contact with said semiconductor layer, a second metal layer is in contact with said first metal layer, and a third layer is in contact with said second layer;

said second metal layer comprises a metal material having a higher melting point than those of the metal materials in said first metal layer and said third metal layer;

said third metal layer comprises a metal material having a lower resistivity than those of the metal materials in said first metal layer and said second metal layer;

said first metal layer comprises any metal material selected from a group comprising $\text{Ni}_{z1}\text{Si}_{1-z1}$ (where, $0.4 \leq z1 \leq 0.75$), $\text{Pt}_{z2}\text{Si}_{1-z2}$ (where, $0.5 \leq z2 \leq 0.75$), $\text{Pd}_{z3}\text{Si}_{1-z3}$ (where, $0.5 \leq z3 \leq 0.85$), $\text{Ni}_{z4}\text{N}_{1-z4}$ (where, $0.5 \leq z4 \leq 0.85$), and $\text{Pd}_{z5}\text{N}_{1-z5}$ (where, $0.5 \leq z5 \leq 0.85$); and

said second metal layer comprises any metal material selected from a group comprising Mo, W, Ta, $\text{Mo}_x\text{Si}_{1-x}$, $\text{Pt}_x\text{Si}_{1-x}$, $\text{W}_x\text{Si}_{1-x}$, $\text{Ti}_x\text{Si}_{1-x}$, $\text{Ta}_x\text{Si}_{1-x}$, $\text{Mo}_x\text{N}_{1-x}$, W_xN_{1-x} , $\text{Ti}_x\text{N}_{1-x}$, and $\text{Ta}_x\text{N}_{1-x}$, (where, $0 < x < 1$).

50. (Currently Amended) [[A]]The semiconductor device according to claim 49, wherein said third metal layer comprises any metal material selected from a group comprising Au, Cu, Al, and Pt.

51. (Currently Amended) [[A]]The semiconductor device according to claim 49, wherein said first metal layer comprises a metal material having a higher work function than that of the metal material in said second metal layer.

52. (Currently Amended) [[A]]The semiconductor device according to claim 51, wherein said first metal layer comprises a metal material having a higher work function than that of the metal material in said third metal layer.

53. (Currently Amended) [[A]]The semiconductor device according to claim 49, wherein the melting point of said second metal layer is 1,000°C or higher.

54. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 49, wherein said semiconductor layer is formed on a multilayered structure comprising a plurality of compound semiconductor layers formed on a substrate.

55. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 54, wherein said substrate comprises any substrate selected from a group comprising a sapphire substrate, a SiC substrate and a GaN substrate.

56. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 49, wherein said semiconductor layer is an $\text{Al}_u\text{Ga}_{1-u}\text{N}$ layer (where, $0 \leq u \leq 1$).

57. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 49, wherein said semiconductor layer is a GaN compound semiconductor electron supplying layer formed on a GaN compound semiconductor channel layer.

58. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 57, wherein said GaN compound semiconductor channel layer comprises a compound semiconductor selected from a group comprising GaN and InGaN, and GaN compound semiconductor electron supplying layer comprises AlGaN.

59. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 49, wherein said semiconductor layer is a GaN compound semiconductor channel layer formed on a GaN compound semiconductor electron supplying layer.

60. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 59, wherein said GaN compound semiconductor channel layer comprises a compound semiconductor selected from a group comprising GaN and InGaN, and said GaN compound semiconductor electron supplying layer comprises AlGaN.

61. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 49, wherein said semiconductor layer is a n-type GaN channel layer.

62. (Currently Amended) A semiconductor device comprising a semiconductor layer comprising a compound semiconductor using $\text{Ga}_v\text{Al}_{1-v}$ (where, $0 \leq v \leq 1$) as a main component

III-elements and N as a main component of the Group V-elements and a Schottky junction metal layer which is in contact with the semiconductor layer, wherein:

said Schottky junction metal layer comprises a laminated structure wherein a first metal layer is in contact with said semiconductor layer and a second metal layer is in contact with said first metal layer;

said first metal layer comprises a metal material having a higher ~~[[meting]]~~melting point than that of the metal material in said second metal layer;

said second metal layer comprises a metal material having a lower resistivity than that of the metal material in said first metal layer: and

said first metal layer comprises any metal material selected from a group comprising $\text{Ni}_y\text{N}_{1-y}$ and $\text{Pd}_y\text{N}_{1-y}$ (where, $0 < y < 1$).

63. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 62, wherein said second metal layer comprises any metal material selected from a group comprising any metal material selected from a group comprising Au, Cu, Al, and Pt.

64. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 62, wherein said first metal layer has a higher work function than said second metal layer.

65. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 62, wherein the melting point of said first metal layer is 1,000°C or higher.

66. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 62, wherein said semiconductor layer is formed on a multilayered structure comprising a plurality of compound semiconductor layers formed on a substrate.

67. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 66, wherein said substrate comprises any substrate selected from a group a sapphire substrate, a SiC substrate, and a GaN substrate.

68. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 62, wherein said semiconductor layer is an $\text{Al}_u\text{Ga}_{1-u}\text{N}$ layer (where, $0 \leq u \leq 1$).

69. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 62, wherein said semiconductor layer is a GaN compound semiconductor electron supplying layer formed on a GaN compound semiconductor channel layer.

70. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 69, wherein said GaN compound semiconductor channel layer comprises a compound semiconductor selected from a group comprising GaN and InGaN, and GaN compound semiconductor electron supplying layer comprises AlGaN.

71. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 62, wherein said semiconductor layer is a GaN compound semiconductor channel layer formed on a GaN compound semiconductor electron supplying layer.

72. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 71, wherein said GaN compound semiconductor channel layer comprises a compound semiconductor selected from a group comprising GaN and InGaN, and said GaN compound semiconductor electron supplying layer comprises AlGaN.

73. (Currently Amended) ~~[[A]]The~~ semiconductor device according to claim 62, wherein said semiconductor layer is a n-type GaN channel layer.

74. (Currently Amended) A semiconductor device comprising a semiconductor layer which comprises a compound semiconductor using $\text{Ga}_v\text{Al}_{1-v}$ (where, $0 \leq v \leq 1$) as a main component of the Group III-elements and N as a main component of the Group V-elements and a Schottky junction metal layer which is in contact with the semiconductor layer, wherein:

said Schottky junction metal layer comprises a laminated structure wherein a first metal layer is in contact with said semiconductor layer and a second metal layer is in contact with said first metal layer;

said first metal layer comprises a metal material having a higher ~~[[meting]]~~melting point than that of the metal material in said second metal layer;

said second metal layer comprises a metal material having a lower resistivity than that of the metal material of said first metal layer: and

said first metal layer comprises any metal material selected from a group comprising $\text{Ni}_{y4}\text{N}_{1-y4}$ and $\text{Pd}_{y5}\text{N}_{1-y5}$ (where, $0.5 \leq y5 \leq 0.85$).

75. (Currently Amended) [[A]]The semiconductor device according to claim 74, wherein said second metal layer comprises any metal material selected from a group comprising Au, Cu, Al, and Pt.

76. (Currently Amended) [[A]]The semiconductor device according to claim 74, wherein said first metal layer has a higher work function than said second metal layer.

77. (Currently Amended) [[A]]The semiconductor device according to claim 74, wherein the melting point of said first metal layer is 1,000°C or higher.

78. (Currently Amended) [[A]]The semiconductor device according to claim 74, wherein said semiconductor layer is formed on a multilayered structure comprising a plurality of compound semiconductor layers formed on a substrate.

79. (Currently Amended) [[A]]The semiconductor device according to claim 78, wherein said substrate comprises any substrate selected from a group comprising a sapphire substrate, a SiC substrate, and a GaN substrate.

80. (Currently Amended) [[A]]The semiconductor device according to claim 74, wherein said semiconductor layer is an $\text{Al}_u\text{Ga}_{1-u}\text{N}$ layer (where, $0 \leq u \leq 1$).

81. (Currently Amended) [[A]]The semiconductor device according to claim 74, wherein said semiconductor layer is a GaN compound semiconductor electron supplying layer formed on a GaN compound semiconductor channel layer.

82. (Currently Amended) [[A]]The semiconductor device according to claim 81, wherein said GaN compound semiconductor channel layer comprises a compound semiconductor selected from a group comprising GaN and InGaN, and said GaN compound semiconductor electron supplying layer comprises AlGaN.

83. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 74, wherein said semiconductor layer is a GaN compound semiconductor channel layer formed on a GaN compound semiconductor electron supplying layer.

84. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 83, wherein said GaN semiconductor channel layer comprises a compound semiconductor selected from GaN and InGaN, and said GaN compound semiconductor electron supplying layer comprises AlGaN.

85. (Currently Amended) ~~[[A]]~~The semiconductor device according to claim 74, wherein said semiconductor layer is a n-type GaN channel layer.

Claims 86 – 89 (Cancelled)